



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

: **Confirmation No. 4804**

Masao YOSHIDA et al.

: Docket No. 2001_1152

Serial No. 09/931,412

: Group Art Unit 3723

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: Examiner G.B.M. NGUYEN

POLISHING APPARATUS

6
Election
C. G. G. G.
1/23/04

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

THE COMMISSIONER IS AUTHORIZED
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ACCOUNT NO. 23-0975

Sir:

This is in response to the Restriction Requirement of December 3, 2003.

Applicants, by their undersigned representative, hereby elect the invention of Group II which is drawn to a method and apparatus for polishing a wafer comprising a processing section, a receiving section, and a position mechanism for aligning a reference position of a wafer, and is represented by claims 5-7 and 13.

Having made the required election, a full examination on the merits of the elected invention is hereby requested.

Respectfully submitted,

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